

C10

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 08-012881

(43)Date of publication of application : 16.01.1996

(51)Int.Cl. C08L 77/00
C08K 3/34

(21)Application number : 06-231748 (71)Applicant : MITSUBISHI CHEM CORP

(22)Date of filing : 27.09.1994 (72)Inventor : KAWAI MICHIO
KAWA MANABU
KISHIMOTO SHINTARO

(30)Priority

Priority number : 05245199 Priority date : 30.09.1993 Priority country : JP
06 88508 26.04.1994
JP

(54) POLYAMIDE RESIN COMPOSITION AND ITS PRODUCTION

(57)Abstract:

PURPOSE: To obtain a composition, having a high strength and rigidity, excellent in ductility, good in molding appearance and excellent in gas barrier properties.

CONSTITUTION: This polyamide resin composition comprises an intercalation compound containing a phyllosilicate having ≥ 30 mequiv./100g cation exchange capacity as a host and a quaternary ammonium ion having a $\geq 12C$ alkyl group as a guest in an amount of 1-20wt.% expressed in terms of inorganic ash content and a polyamide resin having 70-500 number-average polymerization degree. Furthermore, this method for producing the resin composition is provided and a polyamide-based resin composition comprises the polyamide resin and an acid-modified polyolefin resin.

LEGAL STATUS

[Date of request for examination] 15.10.1999

[Date of sending the examiner's decision of
rejection]